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CHANG et al.(10) **Pub. No.: US 2022/0386440 A1**(43) **Pub. Date: Dec. 1, 2022**(54) **EUV RADIATION GENERATION METHODS
AND SYSTEMS**continuation of application No. 15/883,234, filed on
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(2013.01)(21) Appl. No.: **17/818,210**(22) Filed: **Aug. 8, 2022****Related U.S. Application Data**(63) Continuation of application No. 17/248,785, filed on
Feb. 8, 2021, now Pat. No. 11,419,203, which is a
continuation of application No. 16/587,018, filed on
Sep. 29, 2019, now Pat. No. 10,917,959, which is a**ABSTRACT**

A method for generating EUV light includes providing a laser beam having a Gaussian distribution. This laser beam can be then modified from a Gaussian distribution to a ring-like distribution. The modified laser beam is provided through an aperture in a collector and interfaces with a moving droplet target, which generates an extreme ultraviolet (EUV) wavelength light. The generated EUV wavelength light is provided to the collector away from the aperture. In some embodiments, a mask element may also be used to modify the laser beam to a shape.

